Atty Docket No.: 401352

FIG.1

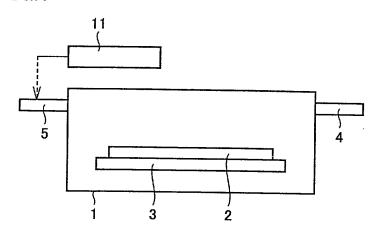


FIG.2

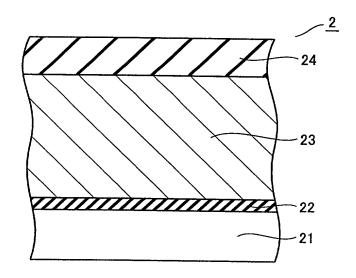


FIG.3

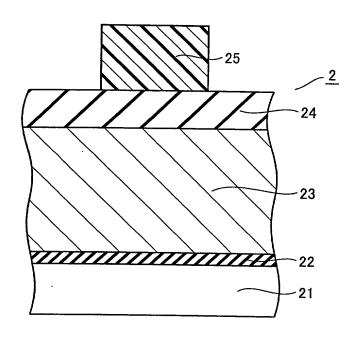


FIG.4

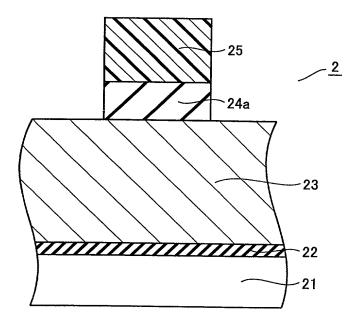


FIG.5

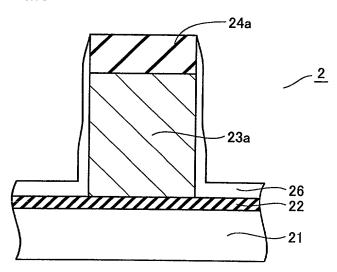


FIG.6

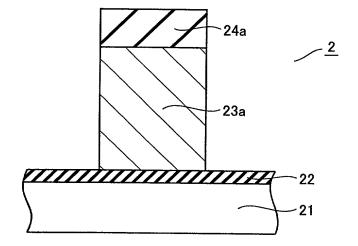
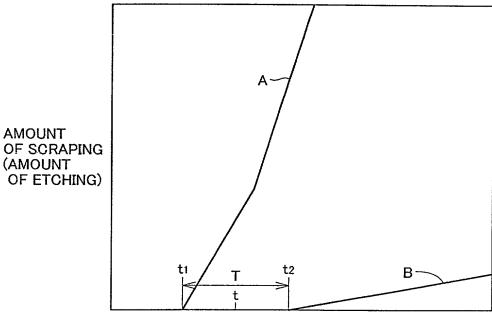


FIG.7



TIME AFTER STARTING SUPPLYING HYDROFLUORIC ACID GAS INTO CHAMBER

FIG.8

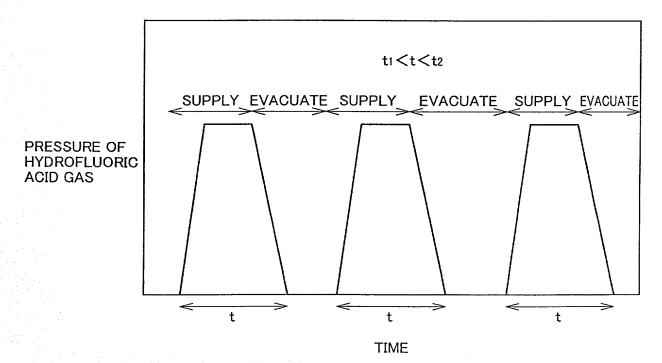


FIG.9

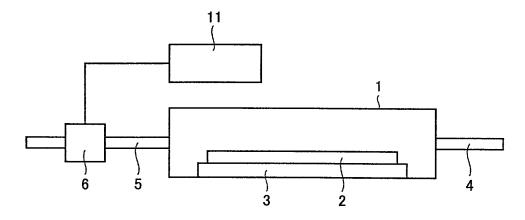


FIG.10

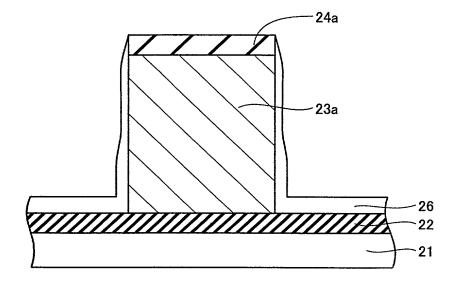


FIG.11

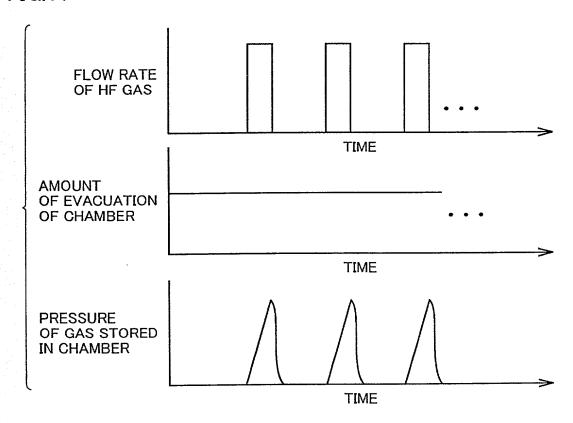
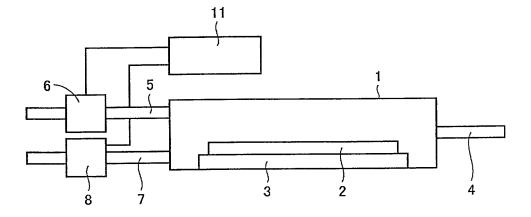


FIG.12





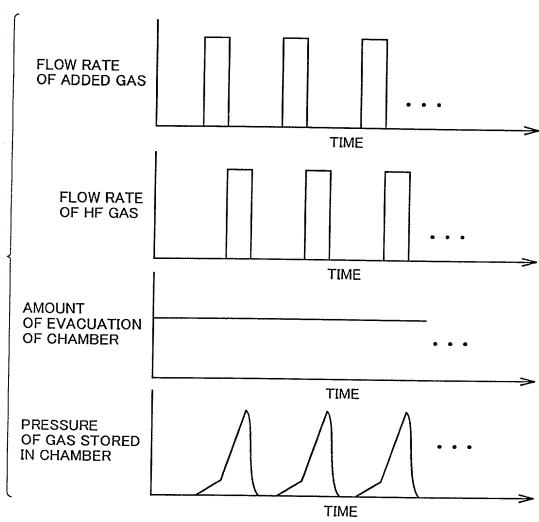


FIG.14

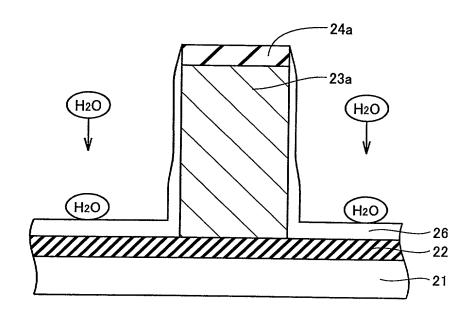


FIG.15

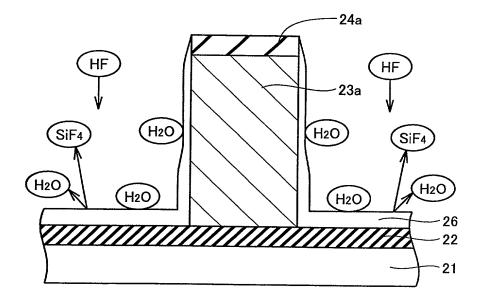
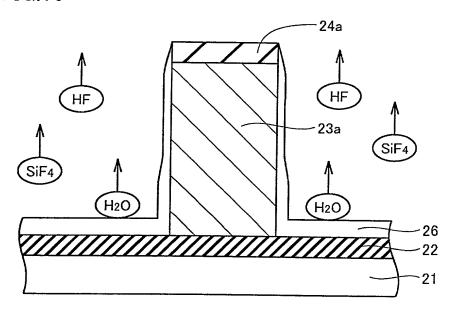
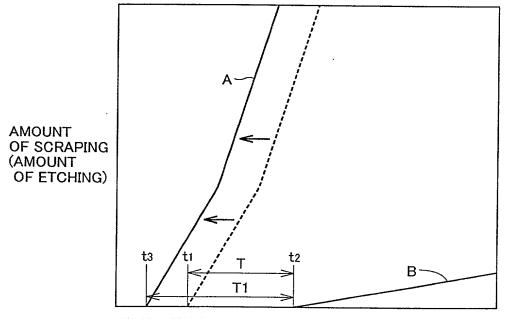


FIG.16



**FIG.17** 



TIME AFTER STARTING SUPPLYING HYDROFLUORIC ACID GAS INTO CHAMBER

FIG.18

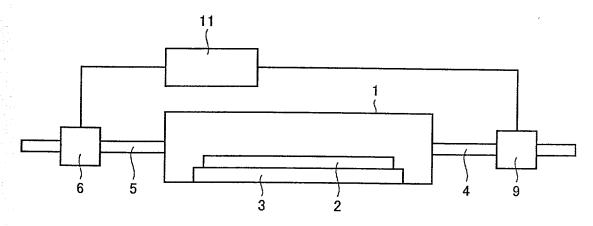


FIG.19

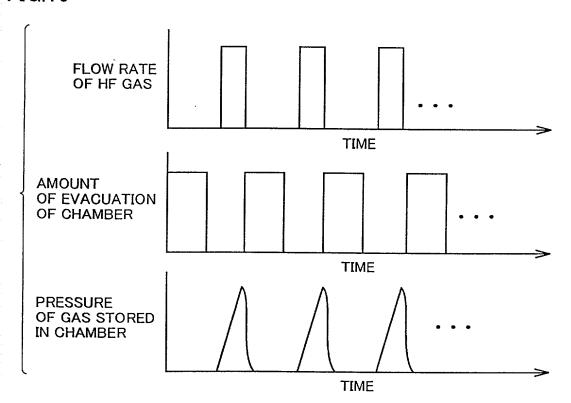


FIG.20

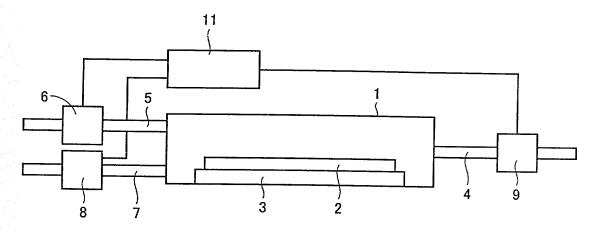
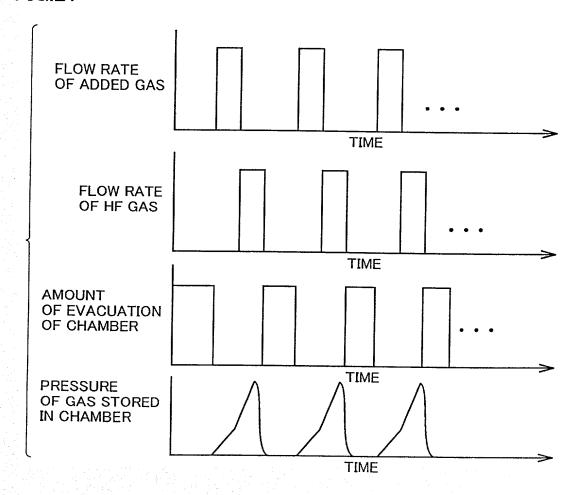


FIG.21



**FIG.22** 

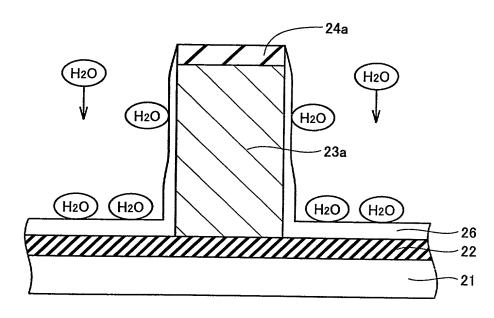
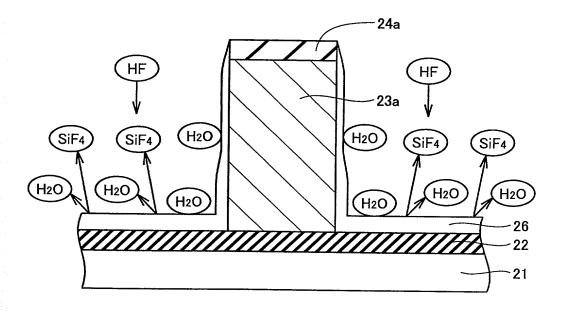
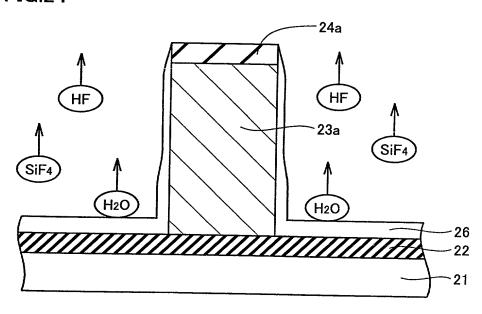


FIG.23

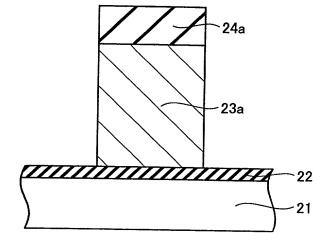


Title: Method of Fabricating Semiconductor Device and Wafer Treatment Apparatus Employed Therefor as well as Semiconductor Device Inventors: SHINTANI ET AL.
Atty Docket No.: 401352
Leydig, Voit & Mayer, Ltd. 202-737-6770

FIG.24



**FIG.25** 



**FIG.26** 

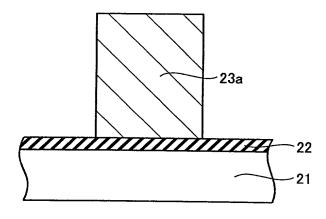


FIG.27 PRIOR ART

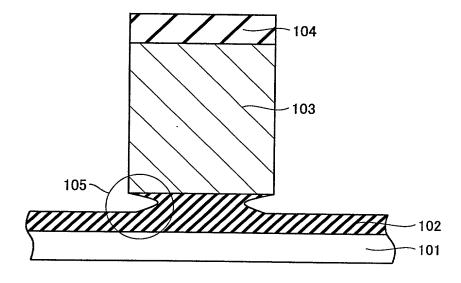
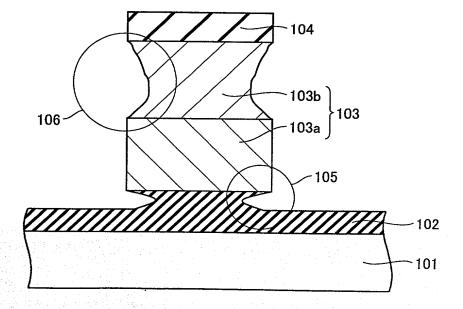


FIG.28 PRIOR ART



Title: Method of Fabricating Semiconductor Device and Wafer Treatment Apparatus Employed Therefor as well as Semiconductor Device

Inventors: SHINTANI ET AL. Atty Docket No.: 401352

FIG.29 PRIOR ART

